FI255 - Tópicos de Óptica e Fotônica II

Óptica Não-Linear

11ª. aula

Prof. Cid B. de Araújo UNICAMP - 25 de maio de 2018

Roteiro

- 1. Técnicas não lineares para caracterização de materiais-Review
- 2. Representação gráfica dos processos não lineares-Review
- 3. Não linearidades de alta ordem
- 4. Cascatas de não linearidades how to eliminate their influence

General theoretical approach

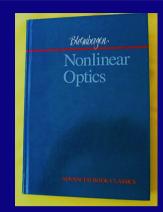
PHYSICAL REVIEW

VOLUME 127, NUMBER 6

SEPTEMBER 15 1962

Interactions between Light Waves in a Nonlinear Dielectric*

J. A. Armstrong, N. Bloemdergen, J. Ducuing, And P. S. Pershan Division of Engineering and Applied Physics, Harvard University, Cambridge, Massachusetts



When there is inversion symmetry:

$$\chi^{(j)} \equiv 0$$

j = even

$$P_L + P_{NL} = \epsilon_0 \sum_{N=0}^{\infty} \chi^{(2N+1)} E^{(2N+1)}$$

$$n_N \propto Re \chi^{(2N+1)}$$

Nonlinear refractive index

$$\alpha_N \propto Im \, \chi^{(2N+1)}$$

Nonlinear absorption coefficient

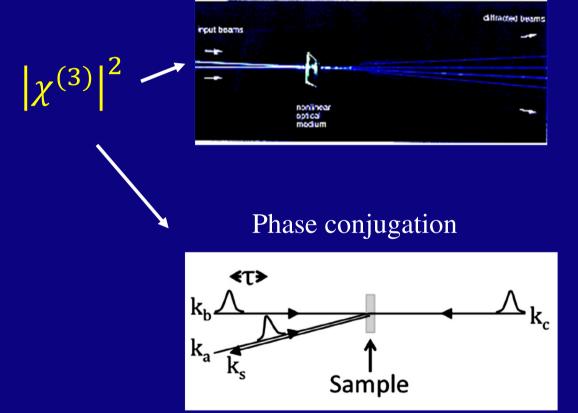
linear + nonlinear

$$n = n_0 + n_2 I + n_4 I^2 + n_6 I^3 + \cdots$$

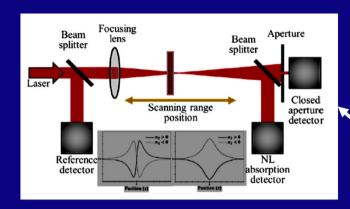
$$\alpha = \alpha_0 + \alpha_2 I + \alpha_4 I^2 + \alpha_6 I^3 + \cdots$$

9ª. aula

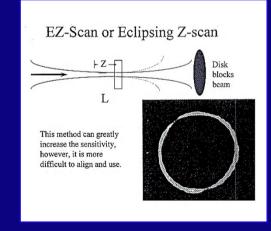
Degenerate four wave-mixing



Z-scan



EZ-scan



Real $\chi^{(3)}$ Im $\chi^{(3)}$

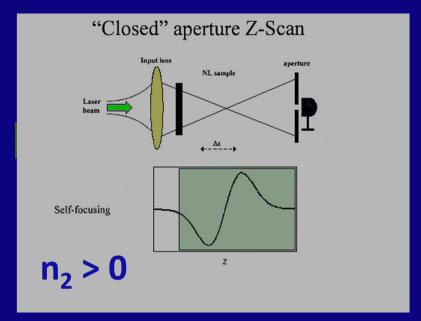
Nonlinear refraction

$$n = n_0 + n_2 I(r)$$

$$I(r) = I_0 \exp [-r^2/w^2]$$

 $n_2 > 0$ self focusing $n_2 < 0$ self defocusing

$$L \ll z_0$$
 $L \ll z_0/\Delta\Phi_0$ $x = z/z_0$ $\Delta\Phi_0 = (n_2I_0)k\ L_{eff}$ $L_{eff} = (1 - e^{-\alpha L})/\alpha$



Sample = lens

$$T(z, \Delta\Phi_0) \cong 1 - \frac{4 \cdot \Delta\Phi_0 \cdot x}{(x^2 + 9)(x^2 + 1)};$$

Sheik-Bahae et al. IEEE J. Quantum Electron. 1990

Z-scan technique Nonlinear absorption

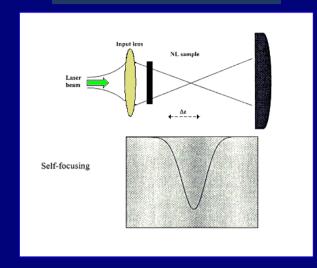
when $\alpha_2 I_0 L_{eff} \ll 1$

$$\Delta T(z) \approx -\frac{\alpha_2 \cdot I \cdot L_{eff}}{2\sqrt{2}} \frac{1}{1 + z^2/Z_0^2}$$

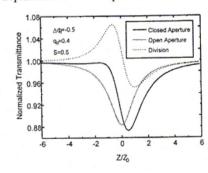
Closed aperture

NL refraction + NL absorption

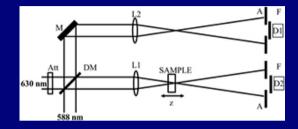
Open aperture



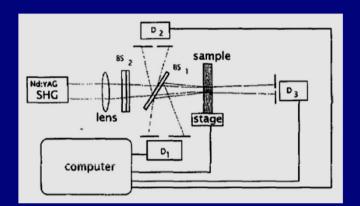
Separation of NLAbsorption and NLRefraction



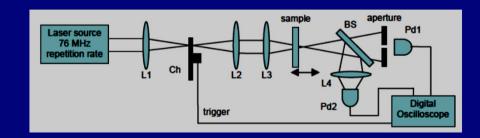
9ª. aula Two-color Z-scan



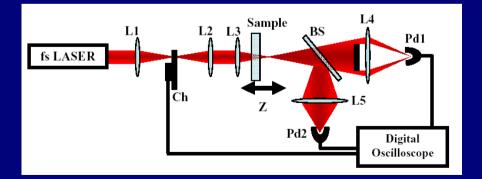
RZ-scan



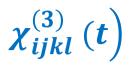
TM Z-scan

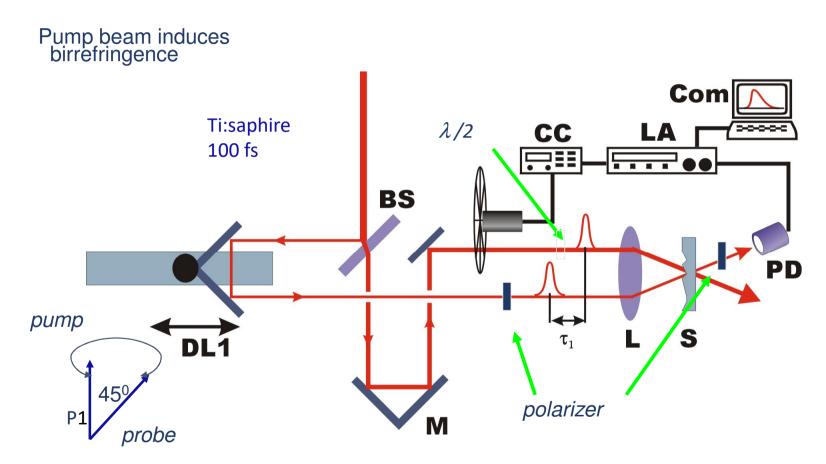


TM- EZ scan



Kerr shutter setup Dynamics of the nonlinearity





Kerr shutter

Isotropic medium

$$\begin{split} \vec{E}_{exc} &= E_{exc} \, \hat{x} \\ \vec{E}_{prova} &= \sqrt{2} \, E_{prova} \, (\hat{x} + \hat{y})/2 \end{split}$$



$$P_x^{(3)} = \chi_{xxxx}^{(3)} |E_{exc}|^2 E_{prova, x}$$

$$P_y^{(3)} = \chi_{yxxy}^{(3)} |E_{exc}|^2 E_{prova, y}$$

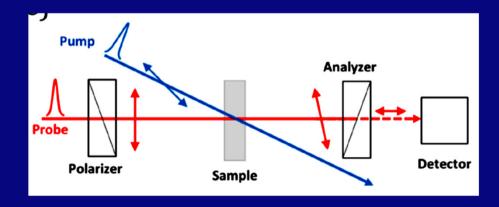
$$\Delta n_x = \frac{2\pi}{n_0} \chi_{xxxx}^{(3)} |E_{exc}|^2$$

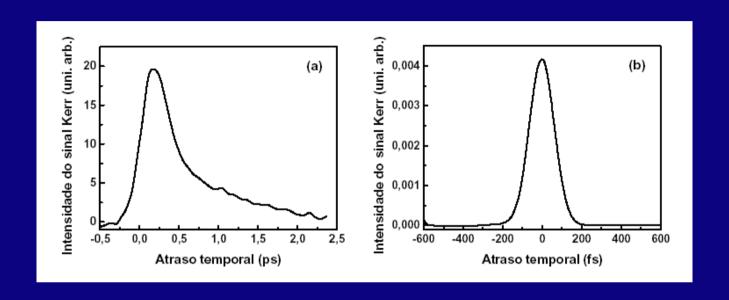
$$\Delta n_y = \frac{2\pi}{n_0} \chi_{yxxy}^{(3)} |E_{exc}|^2$$

$$\Delta n_{NL} = \Delta n_x - \Delta n_y = \frac{4\pi}{3n_0} \chi_{xxxx}^{(3)} \left| E_{exc} \right|^2$$

$$\vec{E}_{prova}(L) = \frac{\sqrt{2}}{2} E_{prova} [\hat{x} + \hat{y} \exp(-i \Delta \phi_{NL})]$$

$$\Delta\phi_{NL}=k\,L\,\Delta n_{NL}$$





Carbon disulfide CS₂

Electronic <50 fs Reorientational > 2ps Silica (Fused SiO₂₎

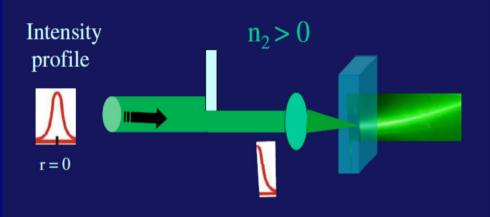
Electronic polarization
Faster than the laser pulse duration

Cross-bending

Appl. Phys. Lett. 63 (1993) 3553

Light-controlled beam deflector in semiconductor doped glasses

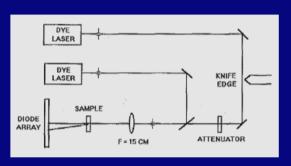
H. Ma and Cid B. de Araújo Departamento de Física, Universidade Federal de Pernambuco, 50732-910 Recife, PE, Brazil

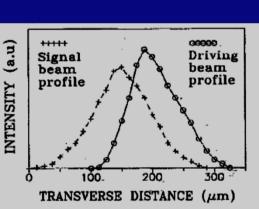


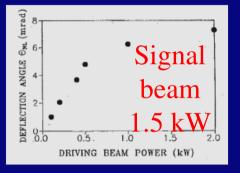
Self-bending-Nonlinear analogue of mirage

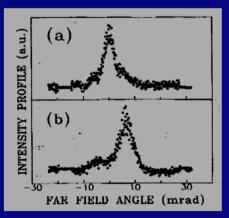
A. E. Kaplan, JETP Lett. 9, 33 (1969).

M. S. Brodin and A. M. Kamuz, JETP Lett. 9, 352 (1969).







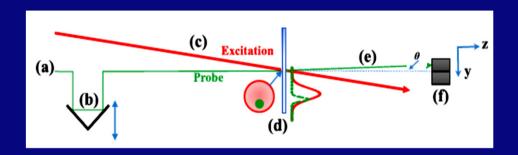


Driving beam peak power: 1.5 kW

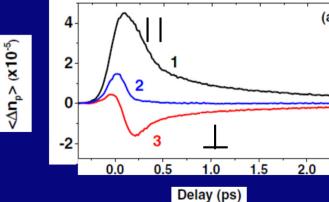
Opt. Lett. 38 (2013) 3518

Beam deflection measurement of time and polarization resolved ultrafast nonlinear refraction

Manuel R. Ferdinandus, Honghua Hu, Matthew Reichert, David J. Hagan, and Eric W. Van Stryland Later and Eric W. Van Stryland



$$\Delta n_p(x,y,t) = \Delta n_p(t) \exp\biggl(\frac{-2(x^2+y^2)}{w_e^2}\biggr)$$



For more details and references for several NL techniques see for example:

IOP Publishing

Rep. Prog. Phys. 79 (2016) 036401 (30pp)

Review

Techniques for nonlinear optical characterization of materials: a review

Cid B de Araújo¹, Anderson S L Gomes¹ and Georges Boudebs²

Four wave-mixing

Phase conjugation

Kerr gate

Scattered Light
Imaging Method –SLIM

Pump-and-probe

Beam deflection techniques

Single beam Z-scan

Two-color Z-scan

Reflection Z-scan

Eclipsing Z-scan

Thermally managed

TM-Z scan

TM-EZ scan

Hartmann - Schack Z-scan

White-light continuum Z-scan

Intensity scan (I-scan)

High-order nonlinearities

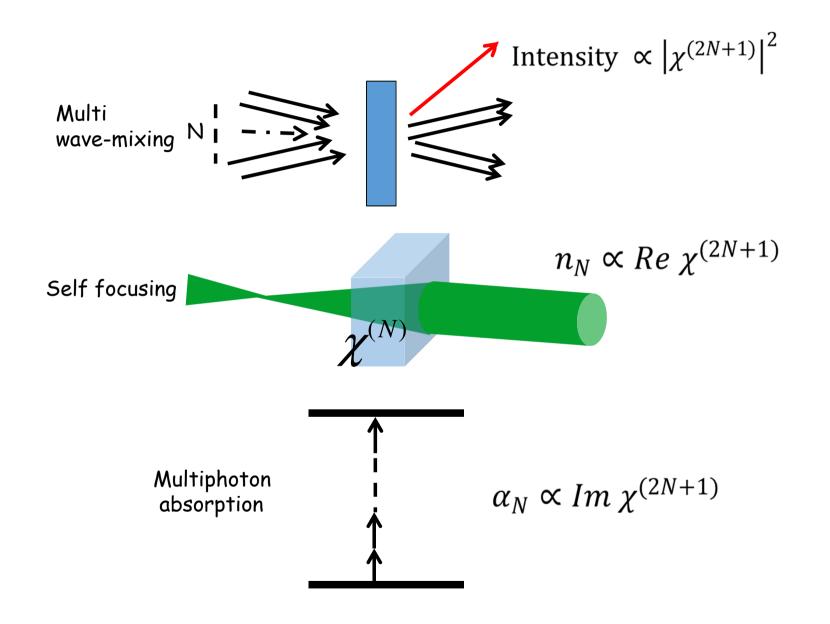
- Generation of higher harmonics
- Multiphoton excitation processes
 - Multi-wave mixing

Studies of multiphoton ionization: 60's; Many studies in the 70's, 80's.

Multiphoton dissociation and ionization processes applied to isotope separation (70's and 80's).

More recently:

Solitons, filamentation, extreme events, generation of VUV and soft X-rays – 400th harmonic, proposals for attosecond X-ray pulse generation



Normally high-order nonlinearities (HON) are weaker than low-order effects

But HON may be due to repeated low-order susceptibilities cascading processes

Macroscopic cascading: involves propagation effects

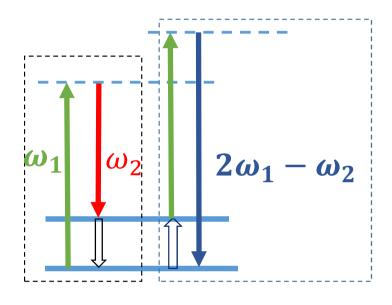
Example: $\omega + \omega$ creates 2ω then $2\omega + \omega$ creates 3ω

Microscopic cascading:

two neighbor atoms interact through local field effects to create a HON process

Meio sem centro de inversão

$$\chi^{(2)} \neq 0$$



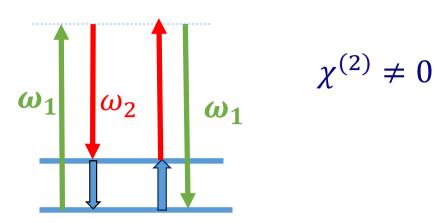
$$E(\omega_1 - \omega_2) \propto \chi^{(2)}(\omega_1 - \omega_2, \omega_1, -\omega_2) E(\omega_1) E^*(\omega_2)$$

$$E(2\omega_1-\omega_2)\propto \chi^{(2)}(2\omega_1-\omega_2,\omega_1-\omega_2,\omega_1)E(\omega_1-\omega_2)E(\omega_1)$$

$$E(2\omega_{1} - \omega_{2}) \propto \chi^{(2)}(2\omega_{1} - \omega_{2}, \omega_{1} - \omega_{2}, \omega_{1})\chi^{(2)}(\omega_{1} - \omega_{2}, \omega_{1}, -\omega_{2})E(\omega_{1})E(\omega_{1})E^{*}(\omega_{2})$$

$$\chi^{(3)}_{off}$$

Outra possibilidade



$$\chi^{(2)} \neq 0$$

$$E(\omega_1 - \omega_2) \propto \chi^{(2)}(\omega_1 - \omega_2, \omega_1, -\omega_2) E(\omega_1) E^*(\omega_2)$$

$$E(\omega_1) \propto \chi^{(2)}(\omega_1, \omega_1 - \omega_2, \omega_2) E(\omega_1 - \omega_2) E(\omega_2)$$

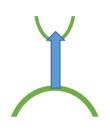
$$E(\omega_1) \propto \chi^{(2)}(\omega_1, \omega_1 - \omega_2, \omega_2) \chi^{(2)}(\omega_1 - \omega_2, \omega_1, -\omega_2) E(\omega_1) E(\omega_2) E^*(\omega_2)$$

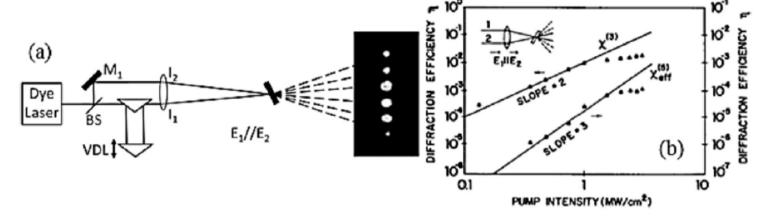
$$\chi_{eff}^{(3)} \propto \left[\chi^{(2)}\right]^2$$

Semiconductor doped glasses

Nanocrystals of CdS_xSe_{1-x}

Rep. Prog. Phys. **79** (2016) 036401





 $\hbar\omega_{laser} \approx E_{gap}$

Figure 2. (a) Typical experimental setup for studying forward DFWM. The photographic image shows the two transmitted beams in the center and self-diffracted orders on each side; (b) measured diffraction efficiency as a function of incident intensity for four-wave and effective six-wave mixing processes (reproduced from [31], copyright 1990 IEEE).



$$\chi_{eff}^{(5)} = A\chi^{(3)}.\chi^{(3)} + B\chi^{(5)}$$

$$2\vec{k}_1 - \vec{k}_2$$

$$\vec{k}_1$$

$$3\vec{k}_1 - 2\vec{k}_2$$

$$-\vec{k}_2$$

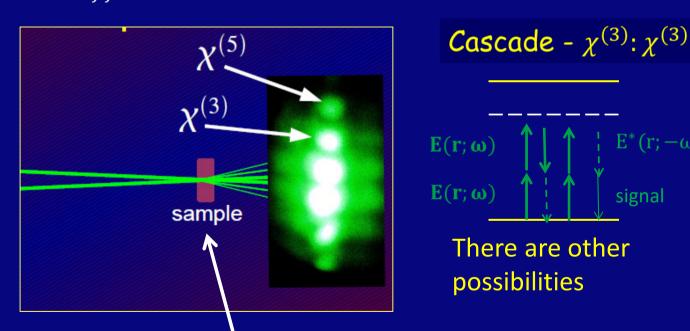
$$\chi^{(3)}.\chi^{(3)} \equiv \chi^{(5)}$$

signal

Observation of a Microscopic Cascaded Contribution to the Fifth-Order Nonlinear Susceptibility

Ksenia Dolgaleva,* Heedeuk Shin, and Robert W. Boyd

$$\chi_{eff}^{(5)} \propto A \chi^{(3)} \colon \chi^{(3)} + B \chi^{(5)}$$



Mixture of CS₂ and Fulerene (C₆₀)

Microscopic cascading by local field effects

Third-order hyperpolarizability

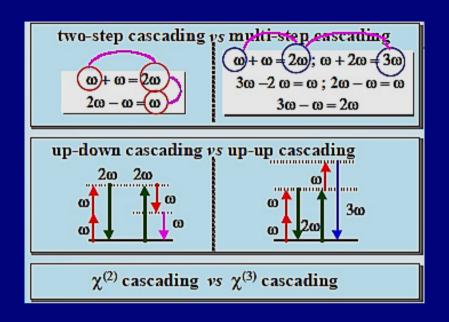
$$\chi^{(3)} = N \gamma_{\text{at}}^{(3)} |L|^2 L^2$$
, factor
$$L = \frac{\varepsilon^{(1)} + 2}{3}$$

Lorentz local field

Direct contribution from the fifth-order hyperpolarizability

$$\chi^{(5)} = N \gamma_{at}^{(5)} |L|^4 L^2 + \frac{24\pi}{10} N^2 (\gamma_{at}^{(3)})^2 |L|^4 L^3 + \frac{12\pi}{10} N^2 |\gamma_{at}^{(3)}|^2 |L|^6 L$$

Contributions by the third-order hyperpolarizability



Under certain conditions, the cascaded contribution can be as large as the direct contribution

Cascaded NL optical processes play important role

- in frequency upconversion
- in optical communications: for routing, switching, information interchange
- for studying fundamental constants of the materials
- for mode-locking and pulse compression

However it is possible determination of pure NL susceptibilities using phase-matching configurations as described in the following papers

Volume 51, number 2

OPTICS COMMUNICATIONS

15 August 1984

DIRECT OBSERVATION OF HIGH-ORDER OPTICAL SUSCEPTIBILITIES VIA ANGULARLY-RESOLVED MULTIWAVE MIXING

R.K. RAJ, O.F. GAO *, D. BLOCH and M. DUCLOY

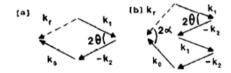


Fig. 1. Wavevector configuration for (a) backward four-wave mixing $(k_0 = -k_1; k_1 = -k_2)$, (b) phase-matched six-wave mixing in which two photons 1 are absorbed and two photons 2 emitted.

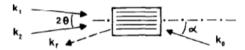


Fig. 3. Grating viewpoint of resonant multiwave mixing. The *n*th-order Bragg condition is given by $\sin \alpha = n \sin \theta$.

$$\chi^{(5)}$$
: sen $\alpha = 2$ sen θ

$$\chi^{(2n+1)}$$
: sen $\alpha = n \operatorname{sen} \theta$

Optics Communications 100 (1993) 193-196

Cascade contributions in the high-order optical nonlinearity measurement

H. Ma, A.S.L. Gomes and Cid B. de Araujo

Phase-matching multi-wave mixing

Unambigous measurement of high-order susceptibilities



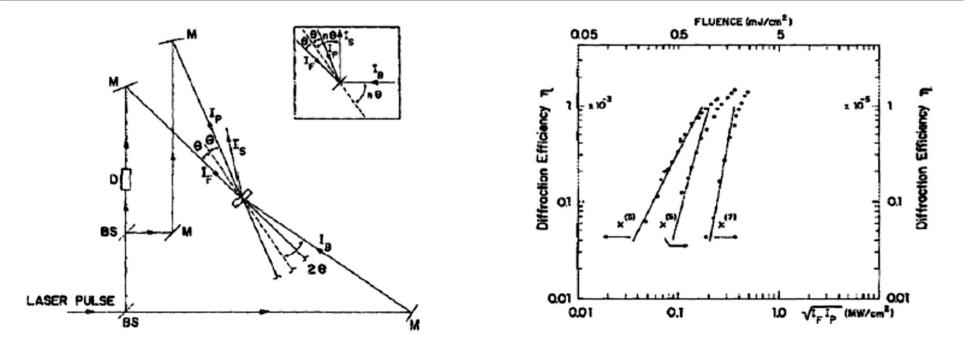
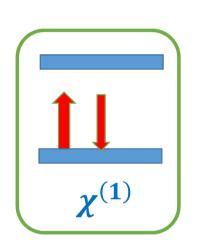
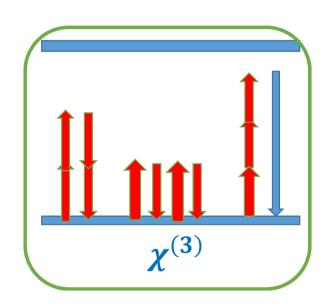


Figure 3. (a) Experimental scheme for unambiguous measurement of phase-matched multi wave-mixing; (b) measured diffraction efficiencies for $|\chi^{(3)}|$, $|\chi^{(5)}|$ and $|\chi^{(7)}|$ in SDG (reproduced from [50], copyright 1988 AIP).

Exemples of pure optical processes

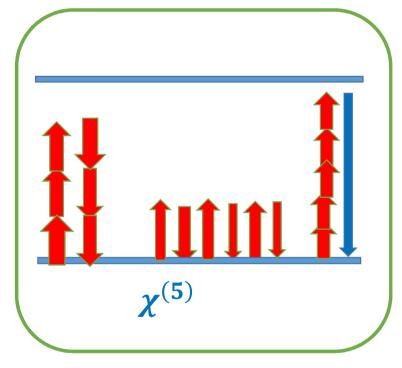


$$P^{(1)} = \epsilon_0 \chi^{(1)} E(\omega)$$



$$P^{(3)} = \epsilon_0 \chi^{(3)} [E(\omega)]^2 E^*(\omega)$$

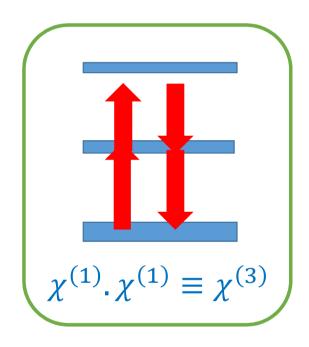
$$P^{(3)} = \epsilon_0 \chi^{(3)} [E(\omega)]^3$$

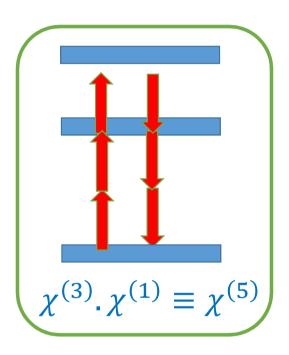


$$P^{(5)} = \epsilon_0 \chi^{(5)} [E(\omega)]^3 [E^*(\omega)]^2$$

$$P^{(5)} = \epsilon_0 \chi^{(5)} [E(\omega)]^5$$

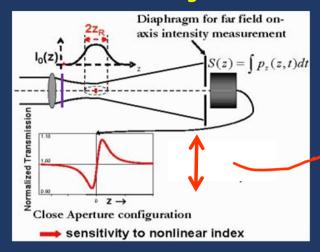
Examples of more cascade processes





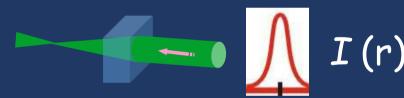
When high-order nonlinearities are present:

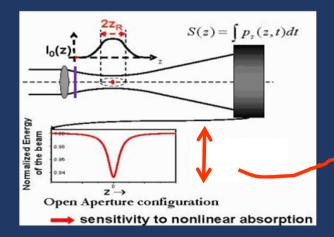
Self - focusing medium



NL refraction
"Closed-aperture" Z scan

$$\Delta T \propto n_2 I + n_4 I^2 + n_6 I^3 + \cdots$$





NL absorption
"Open-aperture" Z scan

$$\Delta T \propto \alpha_2 I + \alpha_4 I^2 + \alpha_6 I^3 + \cdots$$

Particularly for nanocomposites it is possible to vary the material's composition and incident light intensity in order to manage its nonlinearity in such way that the material may present HON on demand.

It means that we may, for instance, to adjust the material's parameters to supress one particular NL susceptibility and enhance the others.

For example, one may supress the third-order refractive index such that the refraction can be dominate by the fifth-order susceptibility

This possibility is illustrated in the next slide where n_2 is canceled but n_4 is not nulled. This nonlinearity management procedure will be the subject presented in the next class.

Observation of fifth-order refraction in a colloid with supressed third-order refraction

